

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Marie Angelopoulos, et al.

**Examiner:** Unassigned

**Serial No:** Unassigned

**Art Unit:** Unassigned

**Filed:** November 22, 2002

**Docket:** YOR920020093US3 (16343ZY)

**For:** ATTENUATED EMBEDDED PHASE  
SHIFT PHOTOMASK BLANKS

**Date:** December 4, 2003

Commissioner for Patents  
P.O.Box 1450  
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT**

Sir:

In accordance with 37 C.F.R. §§1.56, 1.97 and 1.98, it is respectfully requested that the following references, which are also listed on the attached form PTO-1449, be made of record in the above-identified patent application.

1. U.S. Patent No. 6,395,433, dated May 28, 2002, issued to Smith;
2. U.S. Patent No. 6,309,780, dated October 30, 2001, issued to Smith;
3. Burn, J. Lin, "The Attenuated Phase-Shifting Mask", Solid State Technology, January 1992, pp. 43-47; and

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**CERTIFICATE OF MAILING BY "EXPRESS MAIL"**

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I hereby certify that this correspondence is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 C.F.R. §1.10 on the date indicated above and is addressed to the Mail Stop New Patent Application, Commissioner of Patents and Trademarks, Alexandria, Virginia 22313-1450.

Dated: December 4, 2003

  
Steven Fischman

4. Liberman, V. et al., "Materials Issues For Optical Components And Photomasks In 157 NM Lithography", J. Vac. Sci. Technol. B17, November/December 1999, pp. 3273-3279.

Pursuant to 37 C.F.R. §1.98(d), copies of the references listed on the enclosed Form PTO-1449 are not provided since they were previously made of record in parent application Serial No. 10/303,341 filed November 22, 2002. The references were cited in the Information Disclosure Statement filed concurrently with the application on November 22, 2002 and in the Information Disclosure Statement filed July 28, 2003 and in the Information Disclosure Statement filed concurrently with U.S. application No. 10/122,876 on April 12, 2002.

Consideration of this Information Disclosure Statement is respectfully requested, since the information provided herewith may be material to the examination of the present application as defined under 37 C.F.R. §1.56. This statement is not intended to represent that a search has been performed or that no other art than that identified herein exists.

The instant Information Disclosure Statement is being submitted concurrent with the filing of the present application. Therefore, this filing is made under 37 C.F.R. §1.97(b)(1). An Information Disclosure Statement filed under 37 C.F.R. §1.97(b)(1) requires neither certification nor fee.

Respectfully submitted,



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<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <b>YOR920020093US3 (16343ZY)</b>		Application Number <b>Unassigned</b>	
				Applicant(s) <b>Marie Angelopoulos, et al.</b>			
				Filing Date <b>Herewith</b>		Group Art Unit <b>Unassigned</b>	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		6,395,433	05/28/02	Smith			
		6,309,780	10/30/01	Smith			

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>		
		Burn, J. Lin, "The Attenuated Phase-Shifting Mask", Solid State Technology, January 1992, pp. 43-47
		Liberman, V. et al., "Materials Issues For Optical Components And Photomasks In 157 NM Lithography", J. Vac. Sci. Technol. B17, November/December 1999, pp. 3273-3279

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.